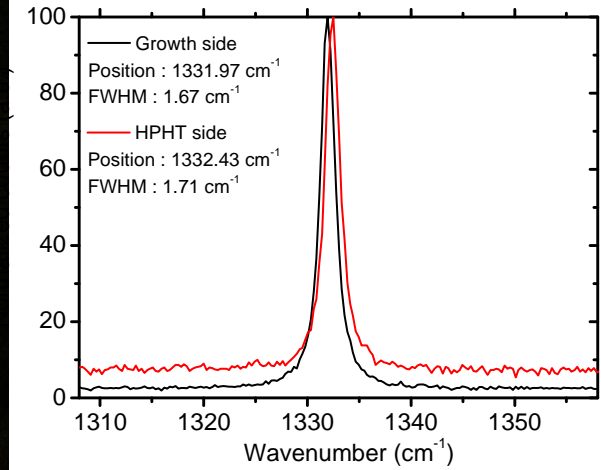
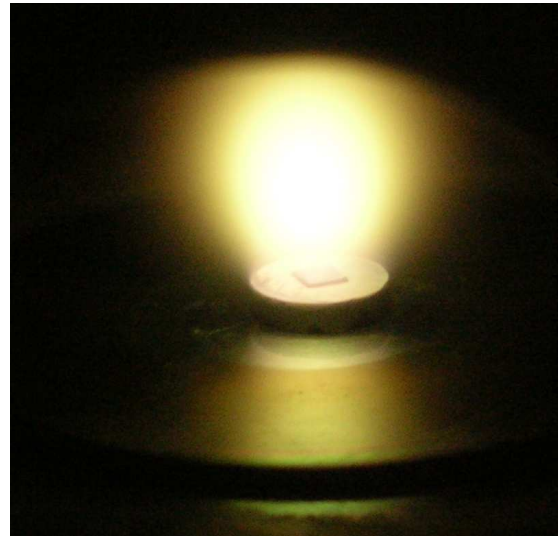
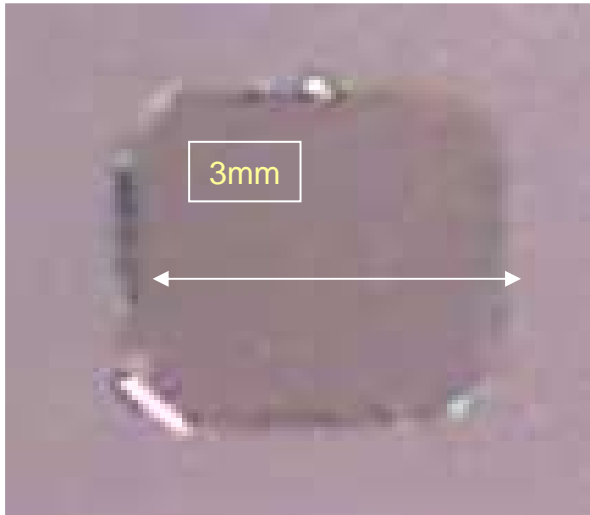




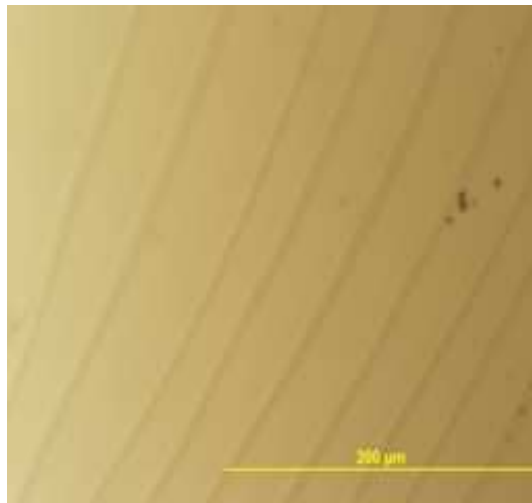
High electronic performance PECVD Single crystal

CEA - Saclay





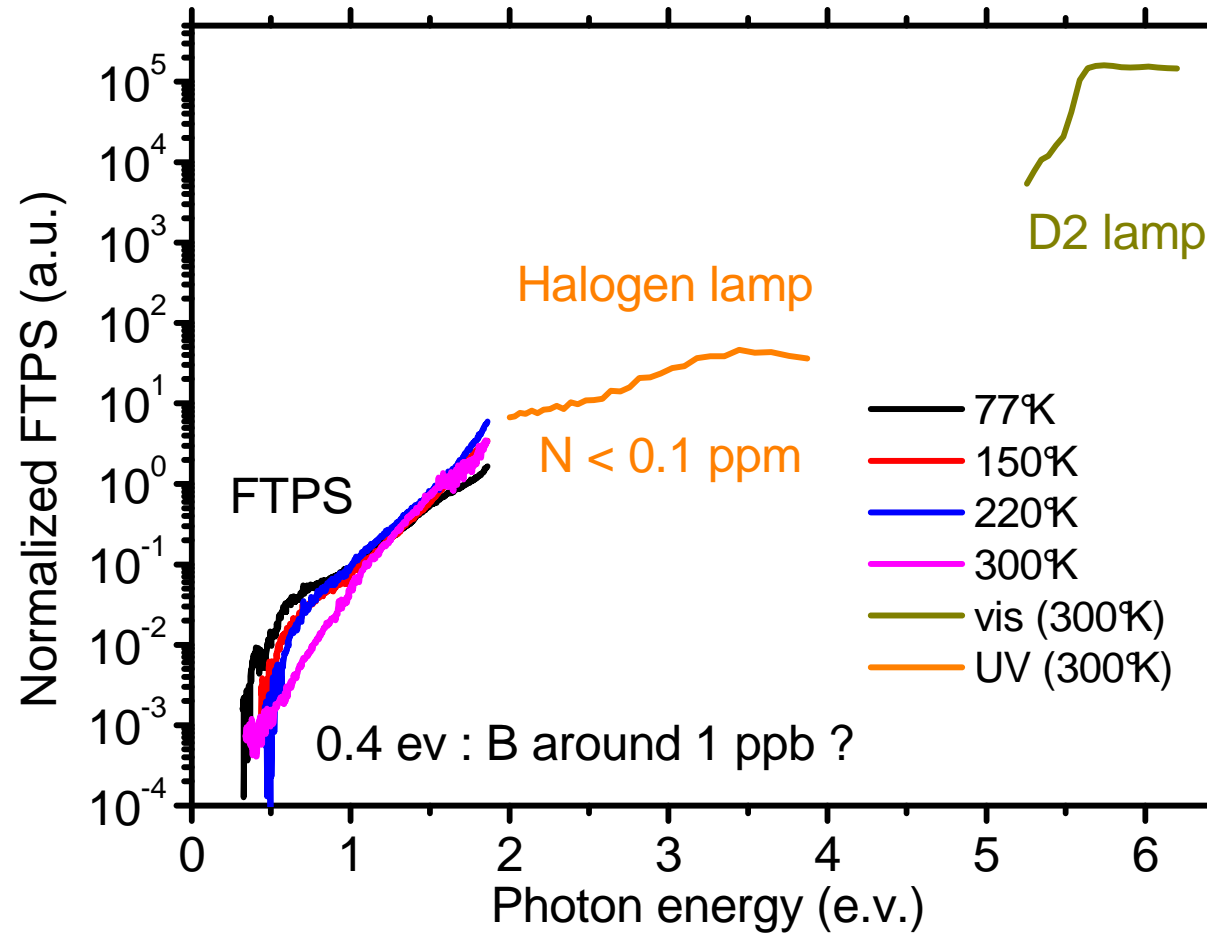
Dense MW plasmas



Surface varying from step flow to atomically flat surfaces

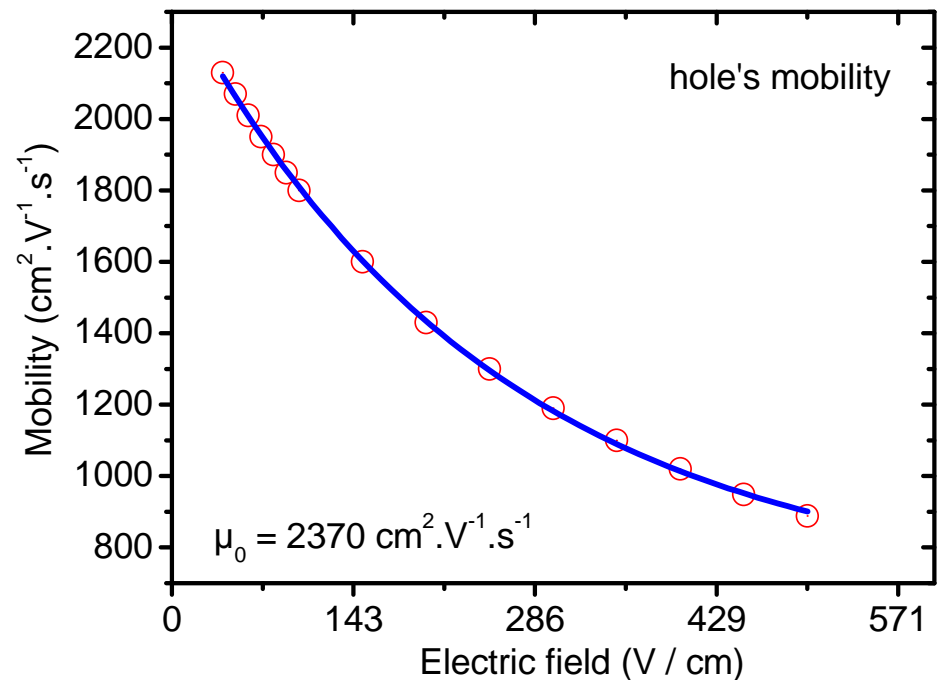
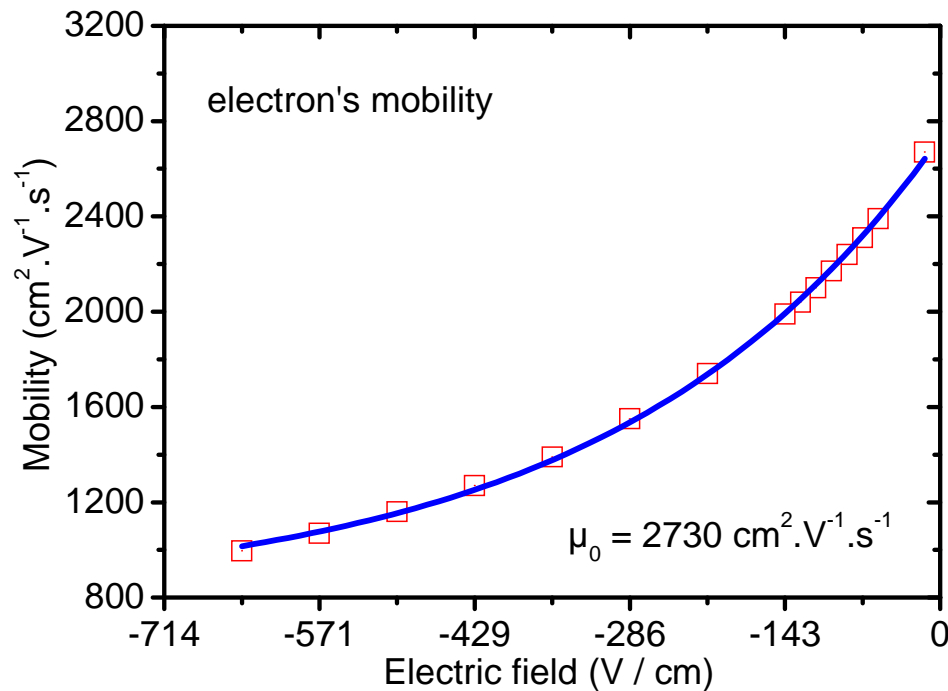


AM- FTPS





TOF using Laser excitation



Higher mobility for electrons than holes

Proposed works in the projects:

- **Optimisation of HPHT surfaces before the growth**
Optimisation of Surface SC CVD surface treatments
(Ion implantation plasma) – smoothening
- **Study of contacts on variously treated smooth surfaces**
(Schottky diodes, Litography)
- **Defect spectroscopy and trapping/recombination kinetics**
(TOF(T), UV, alpha)
- **Further optimisation of growth (high growth rates, plasma configuration)**
- **Doping (B, P) towards devices**
– study of radiation hardness of doped diamond

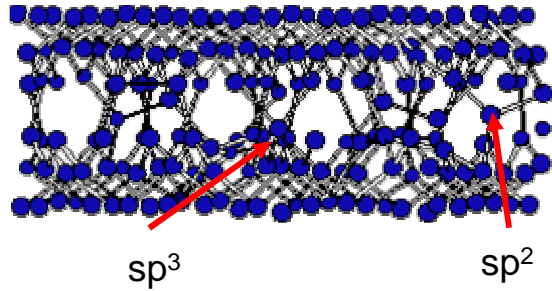
Institute of Physics
Academy of Sciences of the Czech
Republic, Prague

- Dr. Milan Vanecek &..
- Growth of NCD diamond (Aixtron, Linear Antenna)
- Preparation of electronic grade NCD material
- Optical spectroscopy, $\mu\tau(\lambda)$ spectroscopy, AFM, STM, FTPD

Nanocrystalline diamond

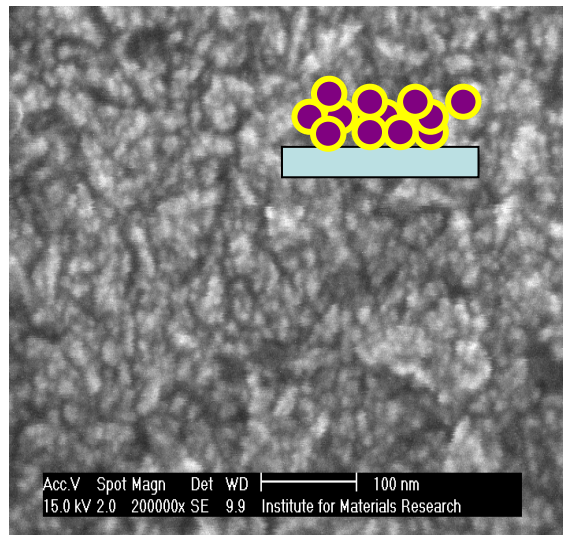
N- UNCD (Argon/CH₄ plasma)

Local metallic conduction



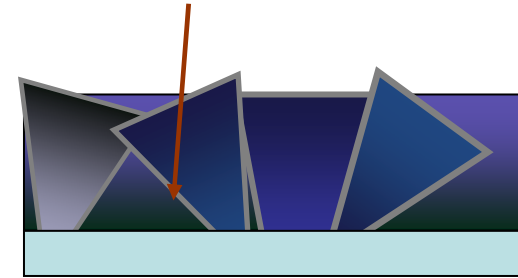
P. Zapol Phys. Rev. B 65 (2001) 045403

5 – 15 nm grain size
remains nano-grained
renucleation

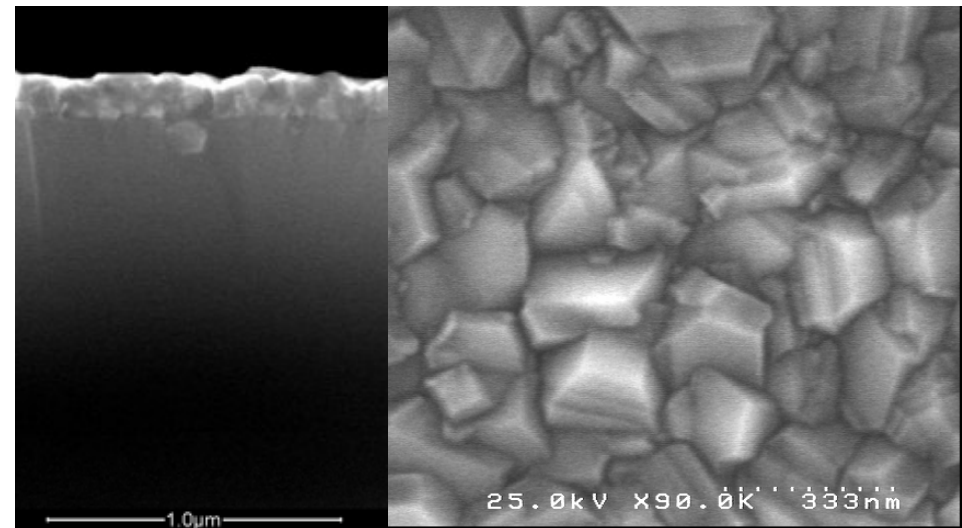


B-NCD (H₂/CH₄ plasma)

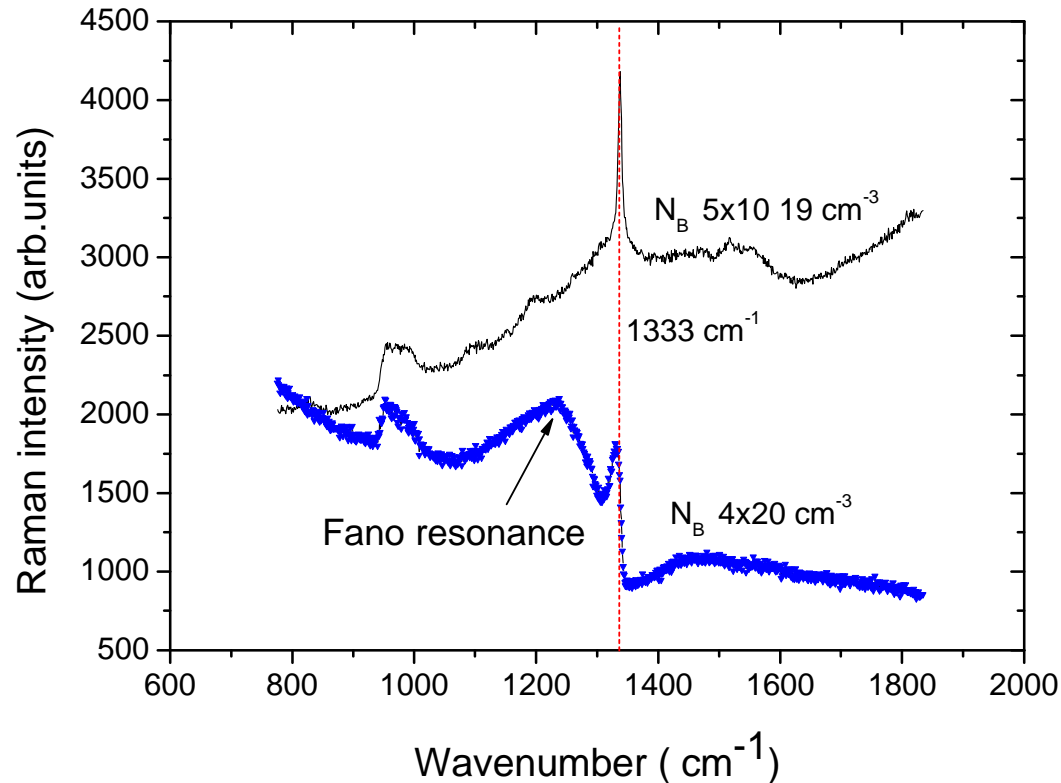
In-grain (MIT) metallic conduction



20 – 100 nm grain size
Films 20- 400 nm thick
Van der Drift, columnar



Raman spectra NCD films (undoped, B-doped)



Raman spectra of variously boron-doped nanocrystalline diamond films with B:C gas doping ratio

800 and 3000 ppm., Central zone phonon at 1332 cm^{-1} is marked by a dash line. The Fano resonance ~ a broad peak at about 1230 cm^{-1} and deformation of the zone-centre phonon line.

Photocurrent in NCD

